

FIG. 1A.

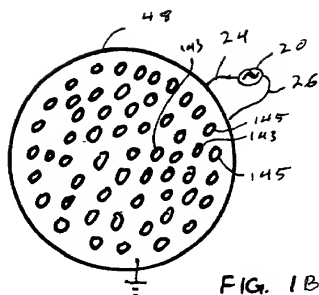


FIG. 1B

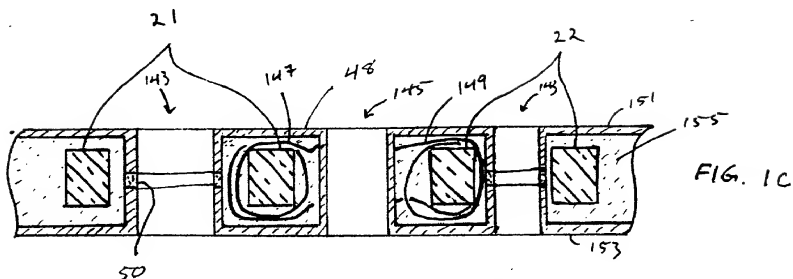


FIG. 1C

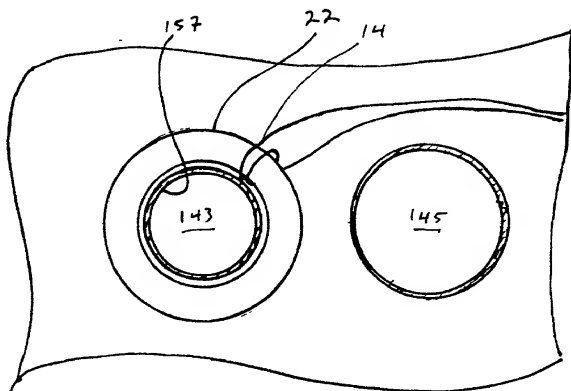
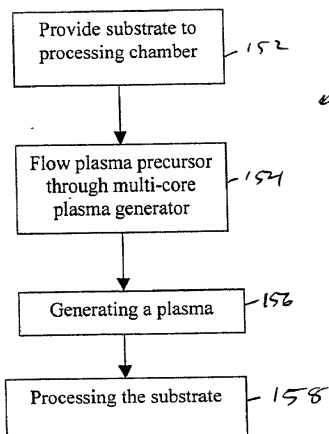


FIG. 1D



150

FIG. 1E

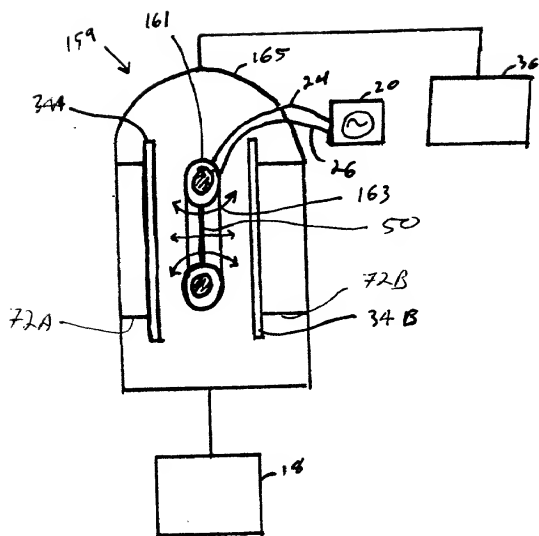


FIG. 2A

Place first and second wafers in the processing chamber each facing an opposite side of the transformer-coupled plasma generator

167

166

FIG. 2B

Form a plasma on both sides of the transformer-coupled plasma generator

168

Simultaneously process both wafers

169

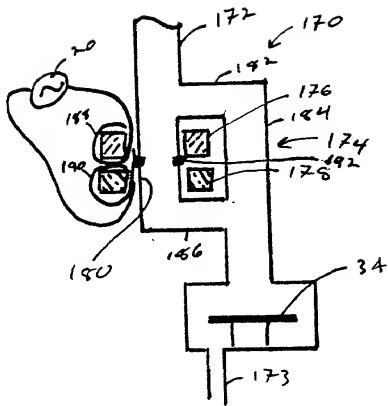


FIG. 3A,

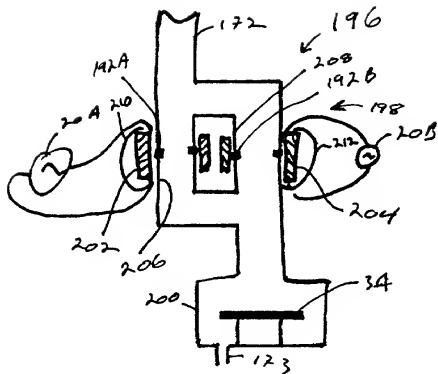


FIG. 3B

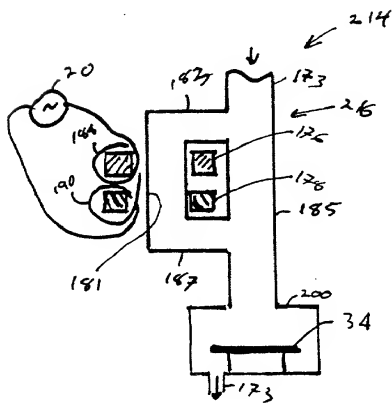


FIG. 3C

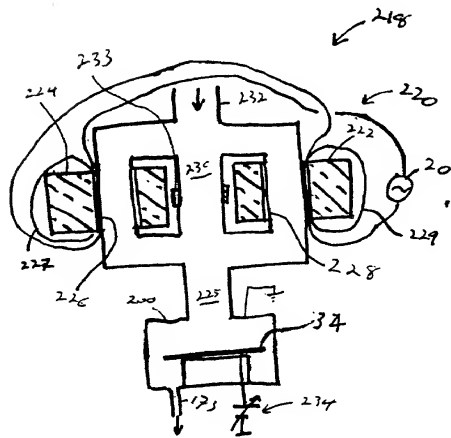


FIG. 3D

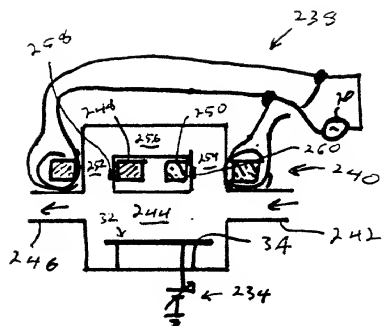


FIG. 3E

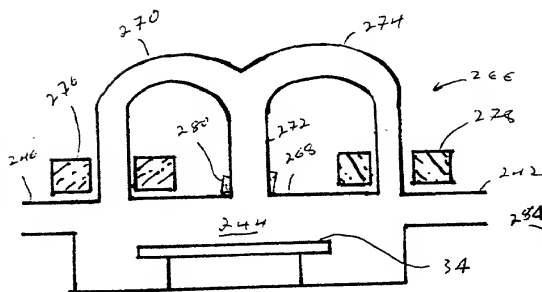


FIG. 3F

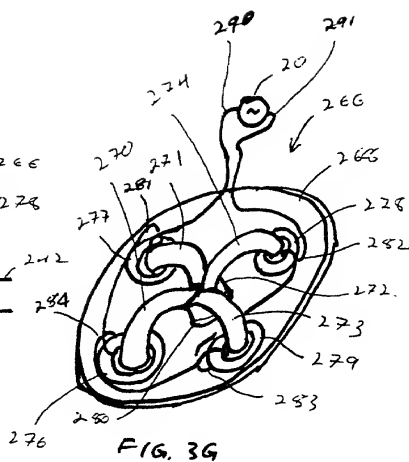


FIG. 3G

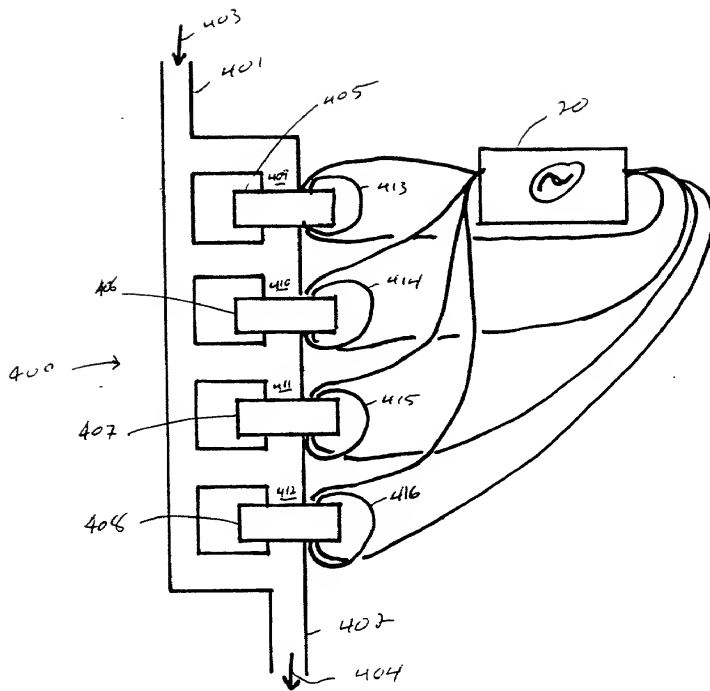
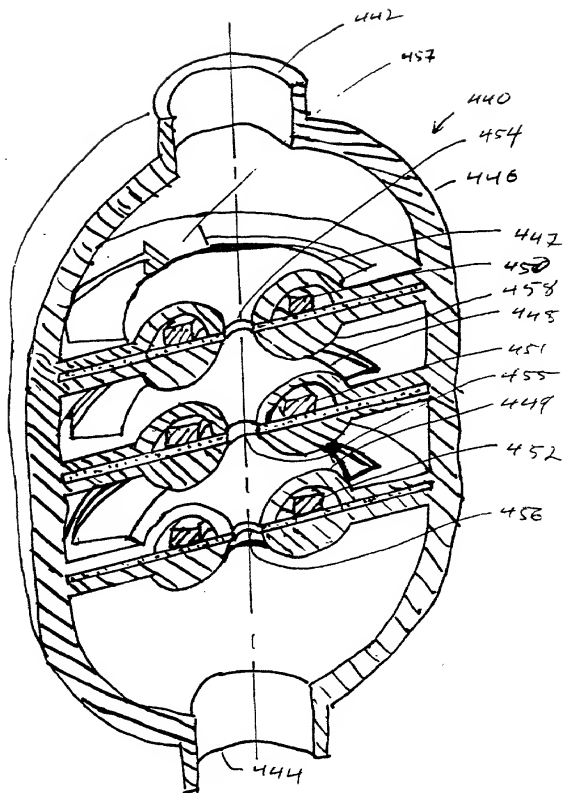


FIG. 4A.



F IG. 4 B.

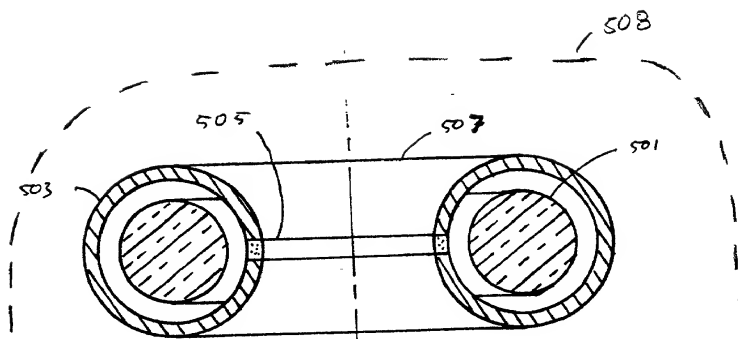
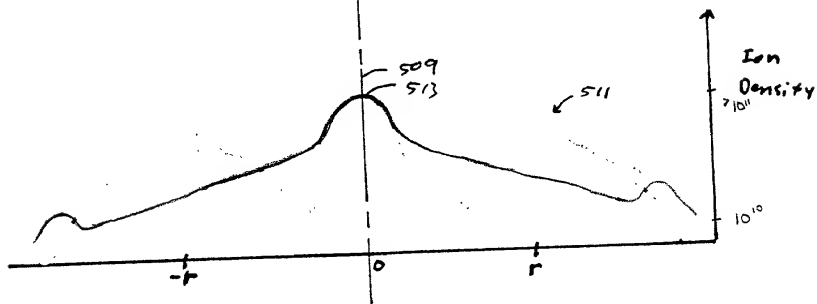
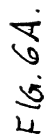


FIG. 5A



Radial Distance

FIG. 5B.



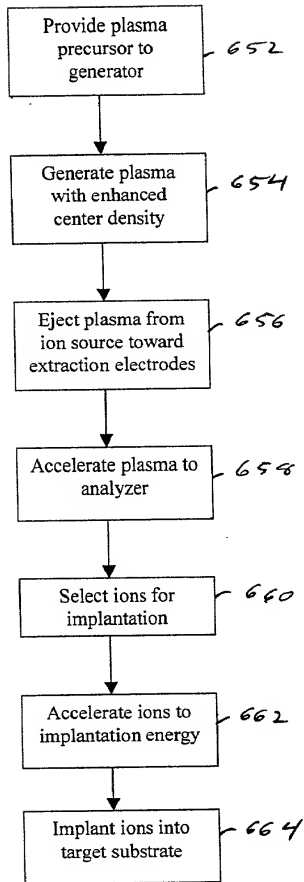


FIG. 6B.

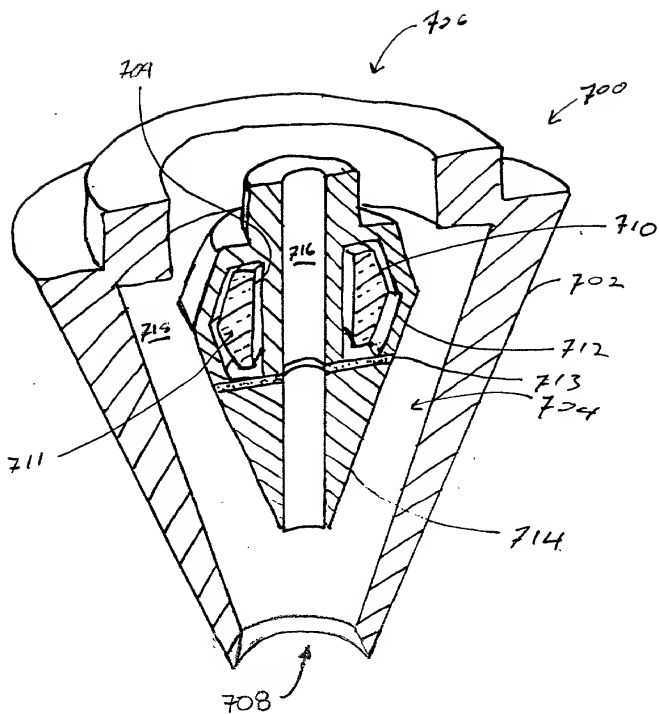


FIG. 7A.

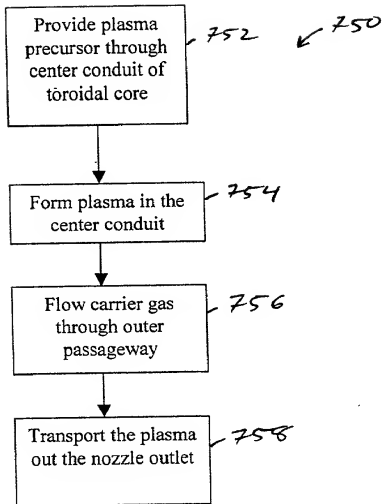


FIG. 7 B

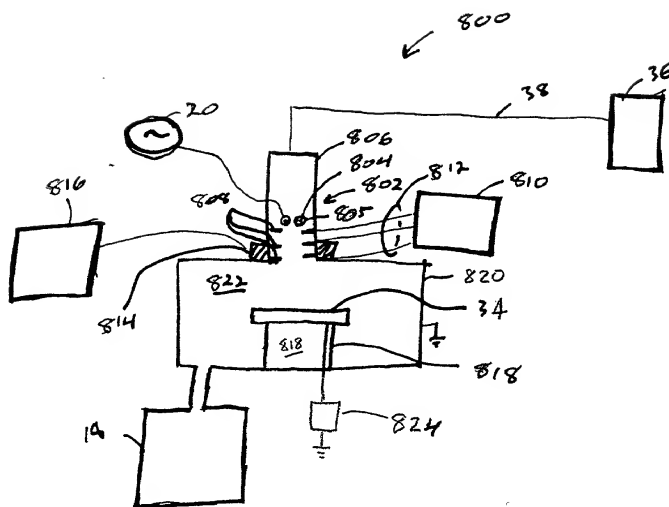
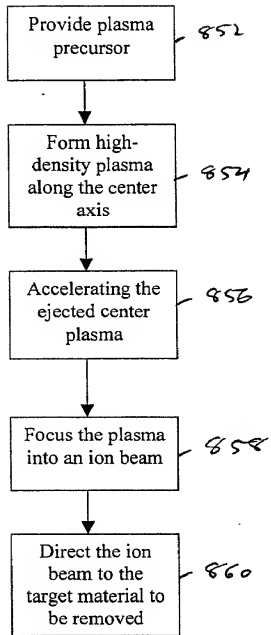


FIG. 8A.



850

FIG. 8B.